PTO/SB/08A (10-01)

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INFORMATION DISCLOSURE STATEMENT BY APPLICANT

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 Application Number
 10/028,198

 Filing Date
 12/20/2001

 First Named Inventor
 Chung J. Lee

 Group Art Unit
 1773

 Examiner Name
 ZACHARIA

 Attorney Docket Number
 108324.0005 DIEL-0004

(use as many sheets as necessary)

Sheet 1 of 4 sheets

U.S. PATENT DOCUMENTS Name of Patentee or Applicant of Document Number **Publication Date** Pages, Columns, Lines, Where Relevant Cite No.1 Examiner Cited Document MM-DD-YYYY Passages or Relevant Number - Kind Code² (if known) Figures Appear SN 09/925,712 08/09/2001 KEZ Lee **Entire Content** 2 US 3,268,599 08/23/1966 Chow **Entire Content** REZ 3 US 3,274,267 09/20/1966 Chow **Entire Content** REZ 4 US 3,280,202 10/18/1966 Gilch **Entire Content** REZ 5 US 3,288,728 11/29/1966 Gorham **Entire Content** 6 07/25/1967 US 3,332,891 Chow et al. **Entire Content** 09/19/1997 REZ US 3,342,754 Gorham, et al. **Entire Content** 8 US 3,349,045 10/24/1967 Gilch **Entire Content** œ 9 US 3,379,803 04/23/1968 **Entire Content** Tittmann, et al. REZ 10 US 3,503,903 03/31/1970 Shaw, et al. REZ **Entire Content** 11 04/28/1970 Entire Content US 3,509,075 Niegish et al. REZ 12 12/07/1971 REZ US 3,626,032 Norris **Entire Content** 13 09/26/1972 REZ US 3,694,495 Norris **Entire Content** REZ 14 US 3,940,530 02/24/1976 Loeb et al **Entire Content** 15 REZ US 5,268,202 12/07/1993 You, et al. **Entire Content** 16 07/23/1996 **Entire Content** US 5,538,758 Beach, et al. 17 REZ US 5,879,808 03/09/1999 Wary, et al. **Entire Content** 18 US 5,958,510 09/28/1999 Sivaramakrishnam, **Entire Content** 19 US 6,130,171 10/10/2000 **Entire Content** REZ Gomi 20 US 6,140,456 **Entire Content** 2EZ 10/31/2000 Foggiator 21 US 6,265,320 07/24/2001 **Entire Content** REZ Shi, et al.

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Examiner Initials*	Cite No. ¹	Country Code ³ - Number ⁴ - Kind Code ⁵ (if known)	Publication Date MM-DD-YYYY	Applicant of Cited Document	Where Relevant Passages or Relevant Figures Appear	T ⁶	
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-	aminer nature	117	Date Considered	8/6/03	

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Complete if Known 10/028,198 Application Number RECEIVED 12/20/2001 Filing Date First Named Inventor Chung J. Lee 1702 (773 Group Art Unit **Examiner Name** Ramsey E. Zacharia Attorney Docket Number 108324.0005 DIEL-0004

			U.S. PATENT [DOCUMENTS	
Examiner Cite No.1	Cite	Document Number	Publication Date	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines, Where Relevan
	No.1	Number - Kind Code ² (if known)	MM-DD-YYYY	Ched Document	Pages, Columns, Lines, Where Relevan Passages or Relevant Figures Appear
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Examiner Initials*	Cite No. ¹	Country Code ³ - Number ⁴ - Kind Code ⁵ (<i>if known</i>)	Publication App		Where Relevant Passages or Relevant Figures Appear	T ⁶		
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Application Number	10/028,198	REC	CE	VE
Filing Date	12/20/2001	Marc	- ^ -	
First Named Inventor	Chung J. Lee	МДТ	13	200,
Group Art Unit	1782-1773	To	0	
Examiner Name	Ramsey E. Zacha	aria I C	77	00
Attorney Docket Number	108324.0005 DIE	L-0004		

		OTHER PRIOR ART NON PATENT LITERATURE DOCUMENTS	
Examiner Initials *	Cite No.1	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.	T ²
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Application Number 10/028,198 Filing Date 12/20/2001 First Named Inventor Chung J. Lee Group Art Unit **Examiner Name** Ramsey E. Zacharia

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108324.0005 DIEL-0004

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	No. ¹ 46 47 48 49 50 51	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published. MORGEN, M., et al., "Morphological Transitions in Fluorinated and Non-Fluorinated Parylenes," Material Research Society Symposium Proceedings, Vol. 565, 1999, pgs. 297-302 [-199] PENG Z., AND MCGIVERN, SEAN., "QUANTUM YIELDS AND ENERGY PARTITIONING IN THE UV PHOTODISSOCIATION OF HALON 2402)", JOUR. OF CHEM.PHYS. VOL 113, NO.17, P7149-7157 (2000). (-2000) PLANO, M. A., et al., "The Effect of Deposition Conditions on the Properties of Vapor-Deposited Parylene AF-4 Films," Material Research Society Symposium Proceedings, Vol. 476, 1997, pgs. 213-218 [-199] RASHED, A.H., "Properties and characteristics of Silicon Carbide." a website publication (www.poco.com), POCO Graphite Inc. 300 old Greenwood Rd., Decatur, TX 76234. [-2002] RIEDEL, W., "ELECTRO-LESS NICKEL PLATING 2 ND EDITION", ASM INTERNATIONAL, FINISHING PUBLICATION LTD. 1998 [-199] RYAN, E. T., et al., "Effect of Deposition and Annealing on the Thermomechanical Properties of Parylene Films," Material Research Society Symposium Proceedings, Vol. 476, 1997, pgs. 225-230 [- 199] SHARMA, A. K., et al., "Optimizing Poly(chloro-p-Xylylene) or Parylene C Synthesis," Journal of Applied Science, John Wiley and Sons, Inc., New York, US, Vol. 36, No. 7, Sept. 20, 1988, pgs. 1555-1565 WARY J, ET AL., POLYMER DEVELOPED TO BE INTERLAYER DIELECTRIC, SEMI-CONDUCTOR

Examiner Signature	136	Date Considered	8/6/03

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